Mask Aligner

P-150



Photolithography is an optical technique for transferring patterns from a glass photo masks onto semiconductor or glass substrates. P-150 is designed for 6" wafers. It has three contacts modes, hard contact, soft contact, and vacuum contact. The aligner has a UV source with 350 watt. The optical power gives 25 mW/cm^2 at 365 nm. It can be used in commercial semiconductor manufacturing or university laboratory settings, wafer fabrication facilities, and MEMS.



Specification

Type	Touch PC Control Manual system	**Wave Length**	350 ~ 450 nm
Mask Size	up to 7 inch × 7 inch	**UV Intensity**	15 ~ 25 / ㎠
Substrate Size	Piece to 6 inch	**UV Beam Uniformity**	3 ~ 5 %
Resolution	1 ㎛	**Contact Mode**	Vacuum / Hard / Soft / Proximity
Alignment Accuracy	1 ㎛	**Microscope**	Dual CCD Zoom Microscope
Lamp & Power supply	350 W	**Option**	IR BSA, CCD BSA

PRO WIN

84, Saneopdanji-ro116beon-gil, Daedeok-gu, Daejeon, 34327, korea
TEL. +82.42.936.8801 FAX. +82.42.936.8802